

IN THE CLAIMS

Please amend Claims 45, 48, and 52 as shown below.

The following is a complete listing of the claims in this application, reflects all changes currently being made to the claims, and replaces all earlier versions and all earlier listings of the claims:

1-40. (Cancelled)

41. (Previously Presented) A method for applying a liquid to a substrate by an ink jet system and detecting an abnormality of the applied liquid on the substrate, the liquid comprising a raw material of an electroconductive film and a solvent thereof, the electroconductive film being arranged to be disposed between electrodes on the substrate and having an electron emitting portion, the method comprising the steps of:

 applying the liquid to the substrate by the ink jet system;
 forming a precursor of the electroconductive film by drying the applied liquid to evaporate the solvent; and
 detecting the abnormality by examining the precursor of the electroconductive film.

42. (Previously Presented) The method according to claim 41, wherein the examining includes a step of examining a forming position of the precursor.

43. (Previously Presented) The method according to claim 41, wherein the examining includes a step of examining a formed shape of the precursor.

44. (Previously Presented) The method according to claim 41, wherein the examining includes a step of examining a foreign substance in the precursor.

45. (Currently Amended) A method for detecting an abnormality of an applied liquid on a substrate, the applied liquid comprising a solvent and a raw material of a thin film to be formed on the substrate and being applied by an ink jet system, and the thin film being a member through which electrons flow, the method comprising the steps of[.]:

- a) forming a precursor of the thin film by drying the applied liquid to evaporate the solvent; and
- b) detecting the abnormality by examining the precursor of the thin film.

46. (Previously Presented) A method according to claim 45, wherein step (b) includes a step of examining a position of the precursor on the substrate.

47. (Previously Presented) A method according to claim 45, wherein step (b) includes a step of examining a shape of the precursor on the substrate.

48. (Currently Amended) A method according to claim 45, wherein step (b) includes a step of examining whether or not the precursor contains ~~an alien substrate a foreign substance.~~

49. (Previously Presented) A method for detecting an abnormality of an applied liquid on a substrate, the applied liquid comprising a solvent and a raw material of a thin film to be formed on an electrode on the substrate and being applied onto the electrode by an ink jet system, and the thin film being a member through which electrons flow, the method comprising the steps of:

- (a) forming a precursor of the thin film by drying the applied liquid to evaporate the solvent; and
- (b) detecting the abnormality by examining the precursor of the thin film.

50. (Previously Presented) A method according to claim 49, wherein step (b) includes a step of examining a shape of the precursor on the substrate.

51. (Previously Presented) A method according to claim 49, wherein step (b) includes a step of examining a shape of the precursor on the substrate.

52. (Currently Amended) A method according to claim 49, wherein step (b) includes a step of examining whether or not the precursor contains ~~an alien substrate a foreign substance.~~